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APPLICATION NO. FILING DATE		FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
09/914,077	09/914,077 08/23/2001		Satoshi Kawamura	0152-0577P	8442	
2292	7590	12/07/2004	EXAMINER			
		KOLASCH & B	LEWIS, MONICA			
PO BOX 74 FALLS CH		VA 22040-0747	ART UNIT	PAPER NUMBER		
				2822		
				DATE MAILED: 12/07/2004		

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)				
		09/914,077	KAWAMURA ET AL.				
Office Action Summary		Examiner	Art Unit				
	•	Monica Lewis	2822				
	- The MAILING DATE of this communic						
Period fo		• •	·				
THE N - Exten after: - If the - If NO - Failur Any re	DRTENED STATUTORY PERIOD FOMALING DATE OF THIS COMMUNIC sions of time may be available under the provisions of SIX (6) MONTHS from the mailing date of this communication for reply specified above is less than thirty (30 period for reply is specified above, the maximum static term of the toreply within the set or extended period for reply eply received by the Office later than three months and patent term adjustment. See 37 CFR 1.704(b).	CATION.  If 37 CFR 1.136(a). In no event, however, may inication.  If days, a reply within the statutory minimum of utory period will apply and will expire SIX (6) Note that the statuter of	a reply be timely filed  thirty (30) days will be considered timely.  ONTHS from the mailing date of this communication.  ABANDONED (35 U.S.C. § 133).				
Status							
1)⊠	Responsive to communication(s) filed	d on 29 September 2004.					
		b)⊠ This action is non-final.					
3)□	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.						
Dispositi	on of Claims						
5)□ 6)⊠ 7)□							
Applicati	on Papers						
10)⊠	The specification is objected to by the The drawing(s) filed on <u>05 December</u> Applicant may not request that any object Replacement drawing sheet(s) including The oath or declaration is objected to	2002 is/are: a)  accepted or bytion to the drawing(s) be held in abey the correction is required if the drawi	vance. See 37 CFR 1.85(a). ng(s) is objected to. See 37 CFR 1.121(d).				
Priority u	nder 35 U.S.C. § 119						
<ul> <li>12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).</li> <li>a) All b) Some * c) None of:</li> <li>1. Certified copies of the priority documents have been received.</li> <li>2. Certified copies of the priority documents have been received in Application No</li> <li>3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).</li> <li>* See the attached detailed Office action for a list of the certified copies not received.</li> </ul>							
2) Notice 3) Inform	(s) e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PT nation Disclosure Statement(s) (PTO-1449 or F No(s)/Mail Date <u>5/03:804</u> .	O-948) Paper N	w Summary (PTO-413) lo(s)/Mail Date of Informal Patent Application (PTO-152)				

#### **DETAILED ACTION**

1. This office action is in response to the request for continued examination filed September 29, 2004.

## Continued Examination Under 37 CFR 1.114

2. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 9/29/04 has been entered.

## Response to Arguments

3. Applicant's arguments with respect to claims 1-6, 28 and 29 have been considered but are most in view of the new ground(s) of rejection.

## Specification

4. The lengthy specification has not been checked to the extent necessary to determine the presence of all possible minor errors. Applicant's cooperation is requested in correcting any errors of which applicant may become aware in the specification.

## Claim Rejections - 35 USC § 103

- 5. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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6. Claims 1, 2, 5, 6, 28 and 29 are rejected under 35 U.S.C. 103(a) as obvious over Mori et al. (Japanese Publication No. 08-222695) in view of Inoue (U.S. Patent No. 4,960,983).

In regards to claim 1, Mori et al. ("Mori") discloses the following:

a) a conductor constituting said coil having a plurality of directly contacting layers (22, 26 and 27) (For Example: See Figure 5 and Paragraphs 23-25).

In regards to claim 1, Mori fails to disclose the following:

a) a metal-sputtered layer or alternatively a metal-evaporated layer and a metal plated layer.

However, Inoue discloses the use of sputtering metal layers (For Example: See Column 4 Lines 15-27). It would have been obvious to one having ordinary skill in the art at the time the invention was made to modify the semiconductor of Mori to include sputtering metal layers as disclosed in Inoue because it aids in providing a connection among the various components (For Example: See Column 4 Lines 15-27).

Additionally, the limitation of "metal-sputtered layer or alternatively a metal-evaporated layer and a metal plated layer" makes it a product by process claim. The MPEP § 2113, states, "Even though product -by[-] process claims are limited by and defined by the process, determination of patentability is based upon the product itself. The patentability of a product does not depend on its method of production. If the product in product-by-process claim is the same as or obvious from a product of the prior art, the claim is unpatentable even though the prior product is made by a different process." *In re Thorpe*, 227 USPQ 964, 966 (Fed. Cir. 1985)(citations omitted).

A "product by process" claim is directed to the product per se, no matter how actually made, In re Hirao and Sato et al., 190 USPQ 15 at 17 (CCPA 1976) (footnote 3). See also

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In re Brown and Saffer, 173 USPQ 685 (CCPA 1972): In re Luck and Gainer, 177 USPQ 523 (CCPA 1973); In re Fessmann, 180 USPQ 324 (CCPA 1974); and In re Marosi et al., 218 USPQ 289 (CAFC 1983) final product per se which must be determined in a "product by, all of" claim, and not the patentability of the process, and that an old or obvious product, whether claimed in "product by process" claims or not. Note that Applicant has the burden of proof in such cases, as the above caselaw makes clear.

Finally, since Mori and Inoue are both from the same field of endeavor, the purpose disclosed by Inoue would have been recognized in the pertinent art of Mori.

In regards to claim 2, Mori discloses the following:

a) at least one metal of aluminum, nickel, copper and chromium or alternatively an alloy containing those metals (For Example: See Paragraphs 24 and 25).

In regards to claim 2, Mori fails to disclose the following:

a) a metal-sputtered layer or alternatively a metal-evaporated layer and a metal plated layer.

However, Inoue discloses the use of sputtering metal layers (For Example: See Column 4 Lines 15-27). It would have been obvious to one having ordinary skill in the art at the time the invention was made to modify the semiconductor of Mori to include sputtering metal layers as disclosed in Inoue because it aids in providing a connection among the various components (For Example: See Column 4 Lines 15-27).

Additionally, the limitation of "metal-sputtered layer or alternatively a metal-evaporated layer and a metal plated layer" makes it a product by process claim. The MPEP § 2113, states, "Even though product -by[-] process claims are limited by and defined by the process, determination of patentability is based upon the product itself. The patentability of a product

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does not depend on its method of production. If the product in product-by-process claim is the same as or obvious from a product of the prior art, the claim is unpatentable even though the prior product is made by a different process." *In re Thorpe*, 227 USPQ 964, 966 (Fed. Cir. 1985)(citations omitted).

A "product by process" claim is directed to the product per se, no matter how actually made, In re Hirao and Sato et al., 190 USPQ 15 at 17 (CCPA 1976) (footnote 3). See also In re Brown and Saffer, 173 USPQ 685 (CCPA 1972): In re Luck and Gainer, 177 USPQ 523 (CCPA 1973); In re Fessmann, 180 USPQ 324 (CCPA 1974); and In re Marosi et al., 218 USPQ 289 (CAFC 1983) final product per se which must be determined in a "product by, all of" claim, and not the patentability of the process, and that an old or obvious product, whether claimed in "product by process" claims or not. Note that Applicant has the burden of proof in such cases, as the above caselaw makes clear.

Finally, since Mori and Inoue are both from the same field of endeavor, the purpose disclosed by Inoue would have been recognized in the pertinent art of Mori.

In regards to claim 5, Mori fails to disclose the following:

a) metal-plated layer is formed by resorting to a electroless plating method or alternatively an electroplating method or alternatively a precision electroforming method.

However, the limitation of "electroless plating method or alternatively an electroplating method or alternatively a precision electroforming method" makes it a product by process claim. The MPEP § 2113, states, "Even though product -by[-] process claims are limited by and defined by the process, determination of patentability is based upon the product itself. The patentability of a product does not depend on its method of production. If the product in product-by-process claim is the same as or obvious from a product of the prior art, the claim is unpatentable even

though the prior product is made by a different process." *In re Thorpe*, 227 USPQ 964, 966 (Fed. Cir. 1985)(citations omitted).

A "product by process" claim is directed to the product per se, no matter how actually made, In re Hirao and Sato et al., 190 USPQ 15 at 17 (CCPA 1976) (footnote 3). See also In re Brown and Saffer, 173 USPQ 685 (CCPA 1972): In re Luck and Gainer, 177 USPQ 523 (CCPA 1973); In re Fessmann, 180 USPQ 324 (CCPA 1974); and In re Marosi et al., 218 USPQ 289 (CAFC 1983) final product per se which must be determined in a "product by, all of" claim, and not the patentability of the process, and that an old or obvious product, whether claimed in "product by process" claims or not. Note that Applicant has the burden of proof in such cases, as the above caselaw makes clear.

In regards to claim 6, Mori fails to disclose the following:

a) line width of said coil is not smaller than 7 um, an inter-line distance thereof is not greater than 5 um and the number of turns thereof is not smaller than 20 turns.

However, the applicant has not established the critical nature of the dimension of "7 um, an inter-line distance thereof is not greater than 5 um and the number of turns thereof is not smaller than 20 turns." "The law is replete with cases in which the difference between the claimed invention and the prior art is some range or other variable within the claims. . . In such a situation, the applicant must show that the particular range is critical, generally by showing that the claimed range achieves unexpected results relative to the prior art range." *In re Woodruff*, 919 F.2d 1575, 16 USPQ2d 1934 (Fed. Cir.1990).

In regards to claim 28, Mori fails to disclose the following:

a) a resistance of said metal-plated layer is less than a resistance of said metal sputtered layer or said metal evaporated layer.

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Although Mori fails to specifically disclose the limitations listed above, the same materials are utilized in Mori as in Applicant's invention therefore it would have the same characteristics. Moreover, claim 1 requires that either the conductive layer includes a metal-sputtered layer or, alternatively, a metal-evaporated layer or a metal-plated layer. Since Inoue has been relied upon as a teaching to use a metal-sputtered layer, no metal plated layer is formed. Hence, the resistance of the metal-plated layer will be less than that of the metal-sputtered layer.

Additionally, the limitation of "metal-sputtered layer or alternatively a metal-evaporated layer and a metal plated layer" makes it a product by process claim. The MPEP § 2113, states, "Even though product -by[-] process claims are limited by and defined by the process, determination of patentability is based upon the product itself. The patentability of a product does not depend on its method of production. If the product in product-by-process claim is the same as or obvious from a product of the prior art, the claim is unpatentable even though the prior product is made by a different process." *In re Thorpe*, 227 USPQ 964, 966 (Fed. Cir. 1985)(citations omitted).

A "product by process" claim is directed to the product per se, no matter how actually made, In re Hirao and Sato et al., 190 USPQ 15 at 17 (CCPA 1976) (footnote 3). See also In re Brown and Saffer, 173 USPQ 685 (CCPA 1972): In re Luck and Gainer, 177 USPQ 523 (CCPA 1973); In re Fessmann, 180 USPQ 324 (CCPA 1974); and In re Marosi et al., 218 USPQ 289 (CAFC 1983) final product per se which must be determined in a "product by, all of" claim, and not the patentability of the process, and that an old or obvious product, whether claimed in "product by process" claims or not. Note that Applicant has the burden of proof in such cases, as the above caselaw makes clear.

Finally, since Mori and Inoue are both from the same field of endeavor, the purpose disclosed by Inoue would have been recognized in the pertinent art of Mori.

In regards to claim 29, Mori discloses the following:

- a) the entirety of said coil is formed on a surface of said IC element (For Example: See Figure 1).
- 7. Claim 3 is rejected under 35 U.S.C. 103(a) as obvious over Mori et al. (Japanese Publication No. 08-222695) in view of Inoue (U.S. Patent No. 4,960,983) and McDonough et al. (U.S. Publication No. 2001/0044013).

In regards to claim 3, Mori fails to discloses the following:

a) coil is formed on a surface of said IC element (31) formed with input/output terminals with interposition of an electrically insulative surface passivation film (See Figure 6 and Column 3 Lines 43-45).

However, Droz discloses the use of a coil that is formed on a surface of an IC element with input/output terminals and interposition of an electrically insulative surface passivation film (For Example: See Figure 6 and Column 3 Lines 43-45). It would have been obvious to one having ordinary skill in the art at the time the invention was made to modify the semiconductor of Mori to include the use of a coil that is formed on a surface of an IC element with input/output terminals and interposition of an electrically insulative surface passivation film a coil with chamfered corners as disclosed in Droz because it aids in providing insulation (For Example: See Column 3 Lines 43-47).

Finally, since Mori and Droz are both from the same field of endeavor, the purpose disclosed by Droz would have been recognized in the pertinent art of Mori.

b) IC element and said coil are electrically interconnected through through-holes formed in said surface passivation film and each having a diameter smaller than a line width of said coil.

However, McDonough et al. ("McDonough") discloses the use of a though-holes (19) in the dielectric film (18) (For Example: See Paragraph 52). It would have been obvious to one having ordinary skill in the art at the time the invention was made to modify the semiconductor of Mori to include a through-holes as disclosed in McDonough because it aids in providing electrical contact among the various components (For Example: See Paragraph 52).

Finally, since Mori and McDonough are both from the same field of endeavor, the purpose disclosed by McDonough would have been recognized in the pertinent art of Mori.

8. Claim 4 is rejected under 35 U.S.C. 103(a) as obvious over Mori et al. (Japanese Publication No. 08-222695) in view of Inoue (U.S. Patent No. 4,960,983) and Sakamoto et al. (U.S. Publication No. 2001/0002874).

In regards to claim 4, Mori discloses the following:

a) coil is implemented in a rectangular spiral pattern in a planar shape all or some of corner portions of said rectangular spiral pattern are chamfered.

However, Sakamoto et al. ("Sakamoto") discloses the use of coil (4) with chamfered corners (For Example: See Figure 1). It would have been obvious to one having ordinary skill in the art at the time the invention was made to modify the semiconductor of Mori to include a coil with chamfered corners as disclosed in Sakamoto because it aids in preventing breakage (For Example: See Paragraph 71).

Finally, since Mori and Sakamoto are both from the same field of endeavor, the purpose disclosed by Sakamoto would have been recognized in the pertinent art of Mori.

#### Conclusion

9. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Monica Lewis whose telephone number is 571-272-1838.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Amir Zarabian can be reached on 571-272-1852. The fax phone number for the organization where this application or proceeding is assigned is 703-308-7722 for regular and after final communications. Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0956.

ML

November 30, 2004

Mary Wilczewski <sup>P</sup>rimary Examiner